



Serial No. 10/024,391 - Marked-up Version of  
Specification

5 TITLE OF THE INVENTION

METHOD OF MANUFACTURING SEMICONDUCTOR  
DEVICE AND METHOD OF MANUFACTURING OPTICAL WAVE  
GUIDE

10 BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention generally relates to  
compound semiconductor devices, and more  
particularly, to a method of manufacturing an  
optical semiconductor element used for an optical  
communication and an optical information management.

2. Description of the Related Art

A compound semiconductor has a band struc-  
ture of a direct transition type and acts with light  
reciprocally. Therefore, an optical semiconductor  
device using a compound semiconductor is utilized  
variously in fields of an optical communication and  
an optical information management. A semiconductor  
device of a compound in an InP group, particularly a  
laser diode, is used for forming an optical signal  
transferred in an optical fiber with a ~~wave-length~~  
wavelength in a ~~[[band]]~~ range of 1.3 to 1.55  $\mu\text{m}$ .

In order to improve a laser oscillation  
efficiency, it is essential to provide an electric  
current blocking structure for the laser diode. In  
the electric current blocking structure, a ~~putted~~  
career is shut in a limited area ~~[[of]]~~ in an axial  
direction. Besides, it is also essential to shut a  
light efficiently in the area where the career is  
shut, because the laser oscillation is generated in  
the laser diode due to a stimulated emission.  
Shutting ~~[[a]]~~ the light to a horizontal direction

in the laser diode in the InP group is realized on a basis of a difference of a refractive index between InGaAsP core wave guiding a light and an InP buried layer.

5                   FIG. 1A to 1D are views for explaining a manufacturing process of a laser diode 10 having a buried hetero structure (BH structure) as an electric current blocking structure and optical confinement structure.

10                   Referring to FIG. 1A, a multi-quantum well layer 12 is formed on an n-type InP substrate 11. An InGaAs layer and an InGaAsP layer are grown repeatedly in the multi-quantum well layer 12. A p-type InP clad layer 13 is formed ~~on the~~ in the multi-quantum well layer 12, and a p-type InGaAs contact layer 14 layer is formed on the p-type InP clad layer 13.

20                   In a process shown in FIG. 1B following the process shown in FIG. 1A, a SiO<sub>2</sub> film 15 is formed on the contact layer 14 as an etching protection layer. After forming of the SiO<sub>2</sub> film 15, an active layer mesa stripe is formed by dry etching. The mesa stripe is extended ~~[[to]]~~ in the <011>-direction in FIG. 1B.

25                   In a process shown in FIG. 1C following the process shown in FIG. 1B, the SiO<sub>2</sub> film 15 is used as a selective growth mask. Besides, a crystal growth of an InP buried layers 16A and 16B having high resistances is implemented at both sides of the mesa stripe by a metal organic vapor phase epitaxy (MOVPE) method. The InP buried layers 16A and 16B are formed by Fe doping. During a re-growth process of the InP buried layers 16A and 16B, a growth stop surface (111) B surface is generated, and thereby  
30                   the InP buried layers 16A and 16B have growth configurations in which mask edges of the InP buried layers 16A and 16B are bulged in areas 16a and 16b.

In a process shown in FIG. 1D following a process shown in FIG. 1C, the  $\text{SiO}_2$  film 15 is eliminated. Besides, a p-side electrode 17 is formed on the contact layer 14, and an n-side electrode 18 is formed on a bottom surface of the substrate 11.

Thus, in case of a buried growth of the InP buried layers 16A and 16B when the  $\text{SiO}_2$  film 15 is used as a selective growth mask, it may be difficult to avoid the bulges of the InP buried layers 16A and 16B in the areas 16a and 16b corresponding to edges of the  $\text{SiO}_2$  film 15. This is because a material ~~density~~ concentration is increased partially on the  $\text{SiO}_2$  film 15, because the crystal growth is not generated on a mask of the  $\text{SiO}_2$  film 15. The material is excessively provided on surfaces of the InP buried layers 16A and 16B growing at both sides of the mesa stripe. For instance, during the process shown in FIG. 1C, when the mesa stripe has a height of approximately  $1.5\ \mu\text{m}$ , the InP buried layers 16A and 16B are bulged with a height of approximately  $0.7\ \mu\text{m}$  in areas 16a and 16b of the mask edges.

As described above, during the process shown in FIG. 1D, the p-side electrode 17 is formed on a surface having a step structure. If the p-side electrode 17 is formed by sputtering a Ti film, a Pt film and an Au film in turn, a disadvantage occurs. That is, because the Ti film and the Pt film have a thickness of approximately  $0.1\ \mu\text{m}$  each and the p-side electrode 17 is formed on the surface having the step structure, an electrode layer is broken at a concave-convex part 17a. If the electrode layer is broken, passing of an electric current through such electrode becomes uneven, and thereby an electric deterioration of a device is caused produced.

Meanwhile, an optical integrated circuit element ~~is paid~~ has received attention recently as an important optical semiconductor device. The laser diode, a wave guide, a light-receiving element, and an optical function element are integrated in the optical integrated circuit element. In such [[the]] an optical integrated circuit element, the mesa stripe may be extended to a direction other than  $\langle 011 \rangle$  or a branch point may exist in the mesa stripe. If a ~~buried~~ burying growth of the mesa stripe of the  $\langle 011 \rangle$ -direction is implemented as shown in FIG. 1C, the growth stop surface (111) B surface is generated. However, regarding a ~~buried~~ burying growth of the optical integrated circuit element, an overhang part that a buried layer 23 is extended on a  $\text{SiO}_2$  mask 22 may be generated as shown in FIGS. 3-(A) to 3-(C), because a particular growth stop surface does not exist in the optical integrated circuit element. Here, FIG. 3-(A) is a perspective view of such the optical wave guide; FIG. 3-(B) is a cross-sectional view thereof; and FIG. 3-(C) is a partially enlarged view thereof.

Referring to FIGS. 3-(A) to 3-(C), a  $\text{SiO}_2$  pattern 22 having an opening part is formed on an InP substrate 21. The InP substrate 21 is partially exposed by the opening part. An InP buried layer 23 is formed on an partially exposed surface of the InP substrate 21 by using the  $\text{SiO}_2$  pattern 22 as a mask, through a re-growth process. At this time, [[since]] because the InP buried layer 23 does not have a growth stop surface such as the growth stop surface (111) B surface, the InP buried layer 23 grows to a side beyond the opening part of the  $\text{SiO}_2$  pattern 22. As a result of this, an overhang part 23A is formed on the  $\text{SiO}_2$  pattern 22, as shown in FIG. 3-(C).

As shown in FIG. 4, if an InP layer 24 re-  
grows after the SiO<sub>2</sub> pattern 22 is removed, a  
material gas does not reach a part directly under  
~~part of~~ the overhang part 23A, and thereby a cave  
5 part 23B may be formed thereon. Such ~~[[the]]~~ a cave  
part 23B has a quite different refractive index from  
the InP buried layer 23. Therefore, a light which  
is wave guided in the wave guide is scattered, and  
thereby a loss of light ~~[[loss]]~~ is caused.

10 FIGS. 5A to 5B are views for explaining a  
problem of a laser diode in the case ~~of that in~~  
which a mesa stripe 31M is extended to a direction  
other than the <011>-direction, and InP buried  
layers 32A and 32B are formed on both sides of the  
15 mesa stripe 31M by using a SiO<sub>2</sub> film 33 formed on  
the mesa stripe 31M as a selective growth mask.

In an example shown in FIG. 5A, the mesa  
stripe 31M is extended to an offset direction at an  
angle of 10° from <011>-direction to <010>-direction.  
20 As shown in an enlarged view in FIG. 5A, ~~[[since]]~~  
because the InP buried layers 32A and 32B do not  
have growth stop surfaces, the InP buried layers 32A  
and 32B grows onto the SiO<sub>2</sub> film 33. As a result of  
this, the overhang part is generated on the SiO<sub>2</sub>  
25 film 33.

If the SiO<sub>2</sub> mask 33 is removed by etching  
and an InP layer 34 is grown as covering the InP  
buried layers 32A and 32B and the mesa stripe 31M, a  
vapor material does not reach ~~[[a]]~~ directly under  
30 the area of the overhang part, and thereby cave  
parts 32a and 32b may be formed thereon, as shown in  
an enlarged view in FIG. 5B.

#### SUMMARY OF THE INVENTION

35 Accordingly, it is a general object of the  
present invention is to provide a novel and useful  
method of manufacturing a semiconductor device.

Another and more specific object of the present invention is to provide a method of manufacturing a semiconductor device, in which an InP layer having a convex structure can be flattened  
5 after a growth of the InP layer.

Still another object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) growing an InP layer on a surface of starting growth,  
10 resulting in the InP layer having a convex structure, and (b) wet etching the InP layer by an etchant including hydrochloric acid and acetic acid, and thereby flattening a surface of the InP layer.

A further object of the present invention  
15 is to provide a method of manufacturing a semiconductor device, including the steps of (a) etching an InP layer which shoulders a selective etching mask, has a lower surface area than the selective etching mask, and has a convex structure  
20 on a surface of the InP layer, by an etchant including hydrochloric acid and acetic acid, and (b) flattening a surface of the InP layer except an area under the selective etching mask.

A further object of the present invention  
25 is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is  
30 grown on a n-type InP substrate, the second semiconductor layer having a smaller band gap than InP is grown on the first semiconductor layer, the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the  
35 fourth semiconductor layer made of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure in which the

semiconductor layers are grown, and thereby a mesa stripe is formed on a part including at least the second to forth semiconductor layers, (c) growing a fifth semiconductor layer on the InP substrate on which the mesa stripe is formed, as a lowest surface height of the fifth semiconductor layer from a surface of the substrate is higher than the fourth semiconductor layer, and (d) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on a n-type InP substrate, the second semiconductor layer having a smaller band gap energy than InP is grown on the first semiconductor layer, the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure in which the semiconductor layers are grown, and thereby a mesa stripe is formed on part including at least the second to forth semiconductor layers, (c) growing a fifth semiconductor layer on the InP substrate on which the mesa stripe is formed, as a lowest surface height of the fifth semiconductor layer from a surface of the substrate is higher than the fourth semiconductor layer and as the mesa stripe is covered with the fifth semiconductor layer, and (d) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to  
5 third semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on a n-type InP substrate, the second semiconductor layer having a smaller band gap than InP is grown on the first semiconductor layer, and  
10 the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, (b) etching the semiconductor structure by using a protection pattern formed on the semiconductor structure as a mask, and thereby a mesa stripe including at least  
15 the second and third semiconductor layers is formed, (c) growing a forth semiconductor layer made of p-type InP on the InP substrate on which the mesa stripe is formed, as a lowest surface height of the  
20 of the substrate is higher than an upper surface of the second semiconductor layer and lower than the third semiconductor layer, (d) etching a surface of the  
the fourth semiconductor layer by an etchant including hydrochloric acid and acetic acid,  
25 (e) growing a fifth semiconductor layer made of n-type InP on the fourth semiconductor layer, (f) removing the protection pattern used as a mask in the step of (a) by etching, and (g) growing a  
sixth semiconductor layer made of p-type InP on the  
30 third and fifth semiconductor layers, and growing a seventh semiconductor layer of InGaAs or InGaAsP on the sixth semiconductor layer.

A further object of the present invention is to provide a method of manufacturing a  
35 semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the



first semiconductor layer made of n-type InP is grown on an n-type InP substrate, the second semiconductor layer having a smaller band gap than InP is grown on the first semiconductor layer, the  
5 third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure by using a protection  
10 pattern formed on the semiconductor structure as a mask, and thereby a mesa stripe including at least the second to ~~[[forth]]~~ fourth semiconductor layers is formed, (c) removing the protection pattern by etching, (d) growing a fifth semiconductor layer  
15 made of p-type InP on the substrate where the mesa stripe is formed, as a lowest surface height of the fifth semiconductor layer from a surface of the substrate is higher than the second semiconductor layer and is lower than the ~~[[forth]]~~ fourth  
20 semiconductor layer and as the mesa stripe is included, (e) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid, (f) growing a sixth semiconductor layer made of n-type InP on the  
25 fifth semiconductor layer, as a lowest surface height of the sixth semiconductor layer from a surface of the substrate is lower than the ~~[[forth]]~~ fourth semiconductor layer, (g) etching a surface of the sixth semiconductor layer by an etchant  
30 including hydrochloric acid and acetic acid, (h) growing a seventh semiconductor layer made of p-type InP, as a lowest surface height of the seventh semiconductor layer from a surface of the substrate is higher than the forth semiconductor layer, and  
35 (i) etching a surface of the seventh semiconductor layer by an etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to  
5 fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on an n-type InP substrate, the second semiconductor layer having a smaller band gap energy than InP is grown on the first semiconductor layer,  
10 the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure by using a protection  
15 pattern formed on the semiconductor structure as a mask, and thereby a mesa stripe including at least the second to ~~[[forth]]~~ fourth semiconductor layers is formed, (c) removing the protection pattern by etching, (d) growing a fifth semiconductor layer  
20 made of p-type InP on the substrate where the mesa stripe is formed, as a lowest surface height of the fifth semiconductor layer from a surface of the substrate is higher than the second semiconductor layer and lower than the ~~[[forth]]~~ fourth  
25 semiconductor layer and as the mesa stripe is included, (e) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid, (f) growing a sixth semiconductor layer made of n-type InP on the  
30 fifth semiconductor layer, and growing a seventh semiconductor layer made of p-type InP on the sixth semiconductor layer, (g) etching a surface of the seventh semiconductor layer by an etchant including hydrochloric acid and acetic acid, (h) removing the  
35 ~~[[forth]]~~ fourth semiconductor layer by etching, and (i) growing an eighth semiconductor layer made of p-type InP, and growing a ninth semiconductor layer

made of InGaAs or InGaAsP on the eighth semiconductor layer.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on an n-type InP substrate, the second semiconductor layer having a smaller band gap than InP is grown on the first semiconductor layer, the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure, and thereby a mesa stripe including at least the second to ~~[[forth]]~~ fourth semiconductor layers is formed, (c) growing a fifth semiconductor layer on the substrate where the mesa stripe is formed, as a contact part height between the fifth semiconductor layer and the mesa stripe from a surface of the substrate is higher than the second semiconductor layer and lower than the ~~[[forth]]~~ fourth semiconductor layer and as the mesa stripe is included, (d) growing a sixth semiconductor layer made of p-type InP on the fifth semiconductor layer, and (e) etching a surface of the sixth semiconductor layer by an etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on an n-type InP substrate, the second semiconductor layer having a smaller band gap than

InP is grown on the first semiconductor layer, the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure by using a protection pattern formed on the semiconductor structure as a mask, and thereby a mesa stripe including the third and ~~[[forth]]~~ fourth semiconductor layers is formed, (c) removing the protection pattern by etching, (d) growing a fifth semiconductor layer made of n-type InP on the substrate where the mesa stripe is formed, as a lowest surface height of the fifth semiconductor layer from a surface of the substrate is lower than the ~~[[forth]]~~ fourth semiconductor layer, (e) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid, (f) growing a sixth semiconductor layer made of p-type InP on the fifth semiconductor layer, as a lowest surface height of the sixth semiconductor layer from a surface of the substrate is higher than the ~~[[forth]]~~ fourth semiconductor layer, and (g) etching a surface of the sixth semiconductor layer by an etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a semiconductor structure in which first to fourth semiconductor layers are grown, wherein the first semiconductor layer made of n-type InP is grown on an n-type InP substrate, the second semiconductor layer having a smaller band gap than InP is grown on the first semiconductor layer, the third semiconductor layer made of p-type InP is grown on the second semiconductor layer, and the

fourth semiconductor layer of InGaAs or InGaAsP is grown on the third semiconductor layer, (b) etching the semiconductor structure, and thereby a mesa stripe including the third and ~~[[forth]]~~ fourth semiconductor layers is formed, (c) growing a fifth semiconductor layer made of n-type InP on the substrate where the mesa stripe is formed, as a highest part height of the fifth semiconductor layer from a surface of the substrate is lower than the ~~[[forth]]~~ fourth semiconductor layer, (d) etching a surface of the fifth semiconductor layer by an etchant including hydrochloric acid and acetic acid, (e) growing a sixth semiconductor layer made of p-type InP on the fifth semiconductor layer, as a lowest part height of the sixth semiconductor layer from a surface of the substrate is higher than the ~~forth~~ semiconductor layer, and (f) etching a surface of the sixth semiconductor layer by an etchant including hydrochloric acid and acetic acid.

20           A further object of the present invention is to provide a method of manufacturing an optical wave guide, including the steps of (a) forming a semiconductor structure, wherein the first semiconductor layer made of InP is grown on an InP substrate, the second semiconductor layer having a larger refractive index than a refractive index of the first semiconductor layer is grown on the first semiconductor layer, and the third semiconductor layer made of InP is grown on the second semiconductor layer, (b) etching the semiconductor structure by using a protection pattern formed on the semiconductor structure as a mask, and thereby a mesa pattern including at least the second and third semiconductor layers is formed, (c) growing a ~~[[forth]]~~ fourth semiconductor layer made of InP on the substrate where the mesa stripe is formed in a state where the protection pattern is shouldered by

the mesa pattern, (d) etching a surface of the  
[[forth]] fourth semiconductor layer in a state  
where the protection pattern is shouldered by the  
mesa pattern, by an etchant including hydrochloric  
5 acid and acetic acid, (e) removing the protection  
pattern, and (f) growing a fifth semiconductor layer  
made of InP.

A further object of the present invention  
is to provide a method of manufacturing an optical  
10 wave guide, including the steps of (a) forming a  
semiconductor structure, wherein a first  
semiconductor layer made of InP is grown on an InP  
substrate, a second semiconductor layer having a  
larger refractive index than a refractive index of  
15 the first semiconductor layer is grown on the first  
semiconductor layer, a third semiconductor layer  
made of InP is grown on the second semiconductor  
layer, and a [[forth]] fourth semiconductor layer  
made of InGaAs or InGaAsP is grown on the third  
20 semiconductor layer, (b) forming a mesa pattern  
including at least the second to [[forth]] fourth  
semiconductor layers by etching the semiconductor  
structure, (c) growing a fifth semiconductor layer  
made of InP on the substrate where the mesa pattern  
25 is formed, as the mesa pattern is covered, and (d)  
etching a surface of the fifth semiconductor layer  
by an etchant including hydrochloric acid and acetic  
acid.

A further object of the present invention  
30 is to provide a method of manufacturing a  
semiconductor device, including the steps of (a)  
forming a selective growth mask on an InP substrate,  
(b) forming a semiconductor pattern by selectively  
growing a first semiconductor layer made of InP on  
35 an InP substrate where the selective growth mask is  
formed, selectively growing a second semiconductor  
layer having a smaller band gap than InP on the

first semiconductor layer, and selectively growing a third semiconductor layer made of InP on the second semiconductor layer, and (c) etching a surface of the third semiconductor layer by etchant including  
5 hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a semiconductor device, including the steps of (a) forming a selective growth mask on an InP substrate,  
10 (b) forming a groove by etching uncovered area by the selective etching mask on a surface of the InP substrate, (c) forming a semiconductor structure by growing a first semiconductor layer made of InP on the substrate, growing a second semiconductor layer  
15 having a smaller band gap than InP on the first semiconductor layer, and growing a third semiconductor layer made of InP on the second semiconductor layer, in a state where the selective growth mask is formed on the substrate, (d) removing  
20 the selective growth mask, and (e) etching a surface of the third semiconductor layer by etchant including hydrochloric acid and acetic acid.

A further object of the present invention is to provide a method of manufacturing a multiple  
25 layer optical wave guide, comprising the steps of (a) forming a first growing semiconductor structure by growing a first semiconductor layer made of InP on an InP substrate, growing a second semiconductor layer having a smaller band gap than InP on the  
30 first semiconductor layer, and growing a third semiconductor layer made of InP on the second semiconductor layer, (b) forming a first mesa stripe including at least the second and third semiconductor layers by forming a first protection  
35 pattern on the first growing semiconductor structure and etching the first growing semiconductor structure with the first protection pattern as a

mask, (c) growing a fourth semiconductor layer made of InP having a high resistance on the substrate where the first mesa stripe is formed, in a state where the first protection pattern remains  
5 on the first mesa stripe, (d) etching a surface of the fourth semiconductor layer by etchant including hydrochloric acid and acetic acid, (e) removing the first protection pattern, (f) forming a second semiconductor structure by growing a fifth  
10 semiconductor layer made of InP on the fourth semiconductor layer, growing a sixth semiconductor layer having a smaller band gap than InP on the fifth semiconductor layer, and growing a seventh semiconductor layer made of InP on the sixth  
15 semiconductor layer, (g) forming a second mesa stripe including at least the sixth and seventh semiconductor layers by forming a second protection pattern on the second growing semiconductor structure and etching the second growing  
20 semiconductor structure with the second protection pattern as a mask, (h) growing an eighth semiconductor layer made of InP on the first semiconductor structure where the second mesa stripe is formed, in a state where the second protection  
25 pattern remains on the second mesa stripe, (i) etching a surface of the eighth semiconductor layer by etchant including hydrochloric acid and acetic acid, and (j) removing the second protection pattern by etching.

30 According to the above invention, it is possible to flatten a convex structure generated at an InP layer based on a crystal growth, by wet-etching with an etchant including hydrochloric acid and acetic acid. Besides, it is possible to make a  
35 position of the flat surface correspond with a lowest surface part of the step structure.

Other objects, features, and advantages of



the present invention will be more apparent from the following detailed description when read in conjunction with the accompanying drawings.

5    BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1A is a view for explaining a manufacturing process of a laser diode having a buried hetero structure according to a related art;

10    FIG. 1B is a view for explaining a manufacturing process of a laser diode having a buried hetero structure according to a related art;

FIG. 1C is a view for explaining a manufacturing process of a laser diode having a buried hetero structure according to a related art;

15    FIG. 1D is a view for explaining a manufacturing process of a laser diode having a buried hetero structure according to a related art;

FIG. 2 is a view for explaining a problem in the process shown in FIGS. 1A to 1D;

20    FIG. 3-(A) is a view for explaining a manufacturing process of an optical wave guide;

FIG. 3-(B) is a view for explaining a manufacturing process of an optical wave guide;

25    FIG. 3-(c) is a view for explaining a manufacturing process of an optical wave guide;

FIG. 4 is a view for explaining a problem in the process shown in Fig. 2;

30    FIG. 5A is a view for explaining a manufacturing process of a laser diode and a problem in the process according to another related art;

FIG. 5B is a view for explaining a manufacturing process of a laser diode and a problem in the process according to another related art;

35    FIG. 6 is a view for explaining a principle of the present invention;

FIG. 7 is a view for explaining a principle of the present invention;

FIG. 8 is a view for explaining a principle of the present invention;

FIG. 9A is a view for explaining a principle of the present invention;

5           FIG. 9B is a view for explaining a principle of the present invention;

FIG. 10A is a view for explaining a principle of the present invention;

10           FIG. 10B is a view for explaining a principle of the present invention;

FIG. 11A is a view for explaining a principle of the present invention;

FIG. 11B is a view for explaining a principle of the present invention;

15           FIG. 12A is a view for explaining a principle of the present invention;

FIG. 12B is a view for explaining a principle of the present invention;

20           FIG. 13A is a view for explaining a principle of the present invention;

FIG. 13B is a view for explaining a principle of the present invention;

FIG. 14A is a view for explaining a principle of the present invention;

25           FIG. 14B is a view for explaining a principle of the present invention;

FIG. 15A is a view for explaining a principle of the present invention;

30           FIG. 15B is a view for explaining a principle of the present invention;

FIG. 16A is a view for explaining a principle of the present invention;

FIG. 16B is a view for explaining a principle of the present invention;

35           FIG. 17A is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;

FIG. 17B is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;

5      FIG. 17C is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;

FIG. 17D is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;

10      FIG. 17E is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;

~~FIG. 17F is a view of a manufacturing process of a laser diode of a first embodiment according to the present invention;~~

15      FIG. 18A is a view of a manufacturing process of a laser diode of a second embodiment according to the present invention;

20      FIG. 18B is a view of a manufacturing process of a laser diode of a second embodiment according to the present invention;

FIG. 18C is a view of a manufacturing process of a laser diode of a second embodiment according to the present invention;

25      FIG. 19A is a view of a manufacturing process of a laser diode of a third embodiment according to the present invention;

30      FIG. 19B is a view of a manufacturing process of a laser diode of a third embodiment according to the present invention;

FIG. 19C is a view of a manufacturing process of a laser diode of a third embodiment according to the present invention;

35      FIG. 19D is a view of a manufacturing process of a laser diode of a third embodiment according to the present invention;

FIG. 19E is a view of a manufacturing

process of a laser diode of a third embodiment according to the present invention;

FIG. 19F is a view of a manufacturing process of a laser diode of a third embodiment according to the present invention;

FIG. 20A is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20B is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20C is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20D is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20E is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20F is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 20G is a view of a manufacturing process of a laser diode of a fourth embodiment according to the present invention;

FIG. 21A is a view of a manufacturing process of a laser diode of a fifth embodiment according to the present invention;

FIG. 21B is a view of a manufacturing process of a laser diode of a fifth embodiment according to the present invention;

FIG. 21C is a view of a manufacturing process of a laser diode of a fifth embodiment according to the present invention;

FIG. 21D is a view of a manufacturing process of a laser diode of a fifth embodiment

according to the present invention;

FIG. 21E is a view of a manufacturing process of a laser diode of a fifth embodiment according to the present invention;

5           FIG. 21F is a view of a manufacturing process of a laser diode of a fifth embodiment according to the present invention;

          FIG. 21G is a view of a manufacturing process of a laser diode of a fifth embodiment  
10 according to the present invention;

FIG. 22A is a view of a manufacturing process of a laser diode of a sixth embodiment according to the present invention;

          FIG. 22B is a view of a manufacturing  
15 process of a laser diode of a sixth embodiment according to the present invention;

FIG. 22C is a view of a manufacturing process of a laser diode of a sixth embodiment according to the present invention;

20           FIG. 22D is a view of a manufacturing process of a laser diode of a sixth embodiment according to the present invention;

          FIG. 23A is a view of a manufacturing process of a laser diode of a seventh embodiment  
25 according to the present invention;

FIG. 23B is a view of a manufacturing process of a laser diode of a seventh embodiment according to the present invention;

          FIG. 23C is a view of a manufacturing  
30 process of a laser diode of a seventh embodiment according to the present invention;

FIG. 23D is a view of a manufacturing process of a laser diode of a seventh embodiment according to the present invention;

35           FIG. 23E is a view of a manufacturing process of a laser diode of a seventh embodiment according to the present invention;

FIG. 24A is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

5 FIG. 24B is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

FIG. 24C is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

10 FIG. 24D is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

FIG. 24E is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

15 FIG. 24F is a view of a manufacturing process of a laser diode of a eighth embodiment according to the present invention;

FIG. 25A is a view of a manufacturing process of an optical wave guide of a ninth embodiment according to the present invention;

FIG. 25B is a view of a manufacturing process of an optical wave guide of a ninth embodiment according to the present invention;

25 FIG. 25C is a view of a manufacturing process of an optical wave guide of a ninth embodiment according to the present invention;

FIG. 25D is a view of a manufacturing process of an optical wave guide of a ninth embodiment according to the present invention;

30 FIG. 25E is a view of a manufacturing process of an optical wave guide of a ninth embodiment according to the present invention;

FIG. 26A is a view of a manufacturing process of an optical wave guide of a tenth embodiment according to the present invention;

FIG. 26B is a view of a manufacturing

process of an optical wave guide of a tenth embodiment according to the present invention;

FIG. 26C is a view of a manufacturing process of an optical wave guide of a tenth  
5 embodiment according to the present invention;

FIG. 27A is a view of a manufacturing process of a semiconductor device of an eleventh embodiment according to the present invention;

FIG. 27B is a view of a manufacturing  
10 process of a semiconductor device of an eleventh embodiment according to the present invention;

FIG. 27C is a view of a manufacturing process of a semiconductor device of an eleventh embodiment according to the present invention;

FIG. 28A is a view of a manufacturing  
15 process of a semiconductor device of a twelfth embodiment according to the present invention;

FIG. 28B is a view of a manufacturing  
20 process of a semiconductor device of a twelfth embodiment according to the present invention;

FIG. 28C is a view of a manufacturing process of a semiconductor device of a twelfth embodiment according to the present invention;

FIG. 28D is a view of a manufacturing  
25 process of a semiconductor device of a twelfth embodiment according to the present invention;

FIG. 28E is a view of a manufacturing process of a semiconductor device of a twelfth embodiment according to the present invention;

FIG. 29A is a view of a manufacturing  
30 process of a multiple optical wave guide of a thirteenth embodiment according to the present invention;

FIG. 29B is a view of a manufacturing  
35 process of a multiple optical wave guide of a thirteenth embodiment according to the present invention;

FIG. 29C is a view of a manufacturing process of a multiple optical wave guide of a thirteenth embodiment according to the present invention;

5           FIG. 29D is a view of a manufacturing process of a multiple optical wave guide of a thirteenth embodiment according to the present invention;

10           FIG. 29E is a view of a manufacturing process of a multiple optical wave guide of a thirteenth embodiment according to the present invention;

15           FIG. 29F is a view of a manufacturing process of a multiple optical wave guide of a thirteenth embodiment according to the present invention; and

20           FIG. 29G is a view of a manufacturing process of a multiple optical wave guide of a thirteenth embodiment according to the present invention.

#### DETAILED DESCRIPTION OF THE ~~PREFERED~~ PREFERRED EMBODIMENTS

25           A description regarding embodiments [[of]] according to the present invention will now be given, with reference of FIGS. 6 to 29.

30           FIG. 6 is a view for explaining a relation between etching amounts of a <100>-direction, a <0-11>-direction, and a <011>-direction and an etching time in which an experiment of etching an InP layer having a convex structure is implemented by using a mixed liquid in an experiment of inventors of the present invention. A mixture ratio of hydrochloric acid, acetic acid, and water in the mixed liquid is  
35   1:5:1.

Referring to FIG. 6, etching speeds [[to]]  
in the <100>-direction and the <011>-direction are



approximately 0.05 to 0.7  $\mu\text{m}/\text{min}$ . An etching speed to the  $\langle 0-11 \rangle$ -direction is approximately 5 to 30  $\mu\text{m}/\text{min}$  and approximately 100 times higher than the etching speeds to the  $\langle 100 \rangle$ -direction and the  $\langle 011 \rangle$ -direction. Therefore, if the convex structure of the InP layer is etched by the mixed liquid, a convex of the  $\langle 0-11 \rangle$ -direction is etched with a greatly high rate. As a result of this, a (100)-surface, a (011)-surface, and a (0-1-1)-surface which is equivalent to the (100)-surface and the (011)-surface remain and other surfaces vanish. That is, inventors realized that the (100)-surface, the (011)-surface, or the (0-1-1)-surface appears as a flat surface on the InP layer by wet-etching with the above-mentioned etching liquid.

If the mixture ratio of respective ingredients in the above-mentioned ~~etchant~~ etchant is changed, an absolute value of the etching rate and relative rates to respective surface directions are changed.

FIG. 7 is a view for explaining the relationship between a ~~density~~ concentration ratio X of acetic acid to hydrochloric acid and an etching rate ratio of the  $\langle 0-11 \rangle$ -direction to the  $\langle 100 \rangle$ -direction. That is, the mixture ratio in the ~~etchant~~ etchant of hydrochloric acid, acetic acid, and water is expressed as 1:X:1.

Referring to FIG. 7, the etching rate  $[[\text{to}]]$  in the  $\langle 0-11 \rangle$ -direction is approximately 30 to 100 times higher than the etching rate  $[[\text{to}]]$  in the  $\langle 100 \rangle$ -direction in ~~an any density~~ a concentration area X of acetic acid. Such an etching anisotropy is caused by contents of hydrochloric acid and acetic acid in the ~~etchant~~ etchant. Particularly, it is recognized that an etching rate ratio of 30 or more is achieved in an area of the ~~density~~ concentration ratio X in a range of 1 to 10

of hydrochloric acid and acetic acid. Thus, it is possible to carry out an ~~objection~~ object of the present invention, namely to flatten the InP layer remarkably, by setting the ~~density~~ concentration of  
5 acetic acid in the above-mentioned area in the etchant.

If a ~~density~~ concentration of water in the etchant is changed, the ~~densities~~ concentrations of hydrochloric acid and acetic acid are changed, and  
10 thereby an absolute value of the etching rate is changed. However, the etching anisotropy shown in FIGS. 6 and 7 is not changed and there is no influence to flatten the InP layer.

The etching anisotropy by the etchant of  
15 the present invention can be achieved by adding hydrogen peroxide water to the above-mentioned etchant mixed liquid.

FIG. 8 is a view for explaining a ratio of a <0-11>-direction etching rate to a <100>-direction  
20 etching rate when the convex structure of the InP layer is etched by an etchant of the mixed liquid including hydrochloric acid, acetic acid, and water and added hydrogen peroxide water.

Referring to FIG. 8, an etching anisotropy  
25 of 30 or more is achieved when a composition Y of hydrogen peroxide water is in a range of 0 to 0.3, where the mixture ratio in the ~~etchant~~ etchant of hydrochloric acid, acetic acid, hydrogen peroxide water, and water is 1:1:Y:1.

30 According to the experiment, it was realized that a side etching was not generated under the etching mask, if the etchant of the present invention including hydrochloric acid and acetic acid was applied to a structure in which a SiO<sub>2</sub>  
35 etching mask shown in FIG. 9A was formed on a surface of the convex structure of the InP layer and the InP layer was flattened as shown in FIG. 9B.

Referring to FIG. 9A, a mesa stripe 41M is formed ~~[[to]]~~ in a [011] direction on an InP substrate by using a SiO<sub>2</sub> pattern 42 as an etching mask. InP buried layers 43A and 43B are formed at both sides of the mesa stripe 41M by using the SiO<sub>2</sub> pattern 42 on the mesa stripe 41M as a selective growth mask.

In a process shown in FIG. 9B, the InP buried layers 43A and 43B are etched by using the etchant of the present invention including hydrochloric acid and acetic acid and using the SiO<sub>2</sub> pattern 42 as an etching mask. Thereby, a flat surface ~~consisted of~~ formed by the (100) surface is formed.

In the process shown in FIG. 9B, even if a side wall surface of the above-mentioned mesa stripe 41M is the (0-11) surface of the InP layer etched selectively by the above-mentioned etchant, a substantial side etching is not generated at the mesa stripe 41M as long as the SiO<sub>2</sub> pattern 42 is formed on the mesa stripe 41M. Therefore, the inventors realized that the mesa stripe 41M remains substantially ~~perfectly~~ perfect after a flattening process shown in FIG. 9B is completed.

That is, in the present invention, during the process of flattening of a convex structure of the InP layer by the ~~etchant~~ etchant including hydrochloric acid and acetic acid, a part of the surface of the convex structure of the InP layer is covered with the mask. Thereby, a convex part covered with the mask ~~remains~~ intentionally remains. An area which is not covered with the mask is etched by the above-mentioned etchant, and thereby it is possible to make the area, such as flattening the (100) surface, the (011) surface, or the (0-1-1) surface selectively.

On the other hand, even if the etching mask is formed on the (100) surface, the (011) surface, and the (0-1-1) surface which do not have convex structures and the above-mentioned structure is etched by the mixed liquid of the present invention, the object of the present invention [[that]] which is flattening of the InP layer, is not achieved. In order for the selective flattening of the present invention to be effective, at least part of an area not covered by the mask should be located lower than the area where the etching mask is formed.

An etching rate by using the etchant of the present invention including hydrochloric acid and acetic acid in a compound semiconductor including Ga or As such as InGaAsP or InGaAs is extremely lower than an etching rate in the InP layer. Particularly, if the etchant does not include the hydrogen peroxide water, such a semiconductor layer is not etched substantially. Therefore, as an above-described etching mask for flattening selectively, a compound semiconductor layer including Ga or As such as InGaAsP or InGaAs can be used as well as SiO<sub>2</sub> and SiN.

Next, a description will be given with regard to a convex structure to which the flattening by use of the etchant of the present invention as described above can be applied effectively.

A. Flattening the convex structures formed at edges of a selective growth mask

FIGS. 10A and 10B are views for explaining a state in which an InP layer 53 grows by using a SiO<sub>2</sub> pattern 52 formed on an n-type InP substrate 51 as a selective growth mask and the InP layer 53 is flattened by an etchant including hydrochloric acid and acetic acid.

If a vapor deposition of the semiconductor

layer is implemented on the substrate by using such  
a selective growth mask 52, a material is provided  
excessively to edges of the mask 52. As a result of  
this, a growth rate of the semiconductor layer is  
5 increased.

FIGS. 11A and 11B are views for explaining  
a state in which the  $\text{SiO}_2$  pattern 52 is formed on a  
convex part of the mesa stripe formed on the above  
mentioned InP substrate 51, and InP buried layers  
10 53A and 53B grown at both sides of the convex part  
by using the  $\text{SiO}_2$  pattern 52 as a selective growth  
mask. In this state, as described above, the InP  
buried layers 53A and 53B bulge at both sides of the  
selective growth mask 52 as a result of the increase  
15 of the material density on the selective growth mask  
52.

Therefore, as shown in FIG. 11B, a wet  
etching process in which an etchant of the present  
invention including hydrochloric acid and acetic  
20 acid is used is applied to a structure shown in FIG.  
11A and thereby the InP buried layers 53A and 53B  
are flattened. In the process shown in FIGS. 11A  
and 11B, the selective growth mask 52 is used as an  
etching mask. Even if the selective growth mask 52  
25 is removed by etching prior to the flattening  
process, an equivalent effect can be achieved as  
shown in FIGS. 12A and 12B.

B. Flattening convex structures reflecting  
concave structures prior to the growth

30 FIGS. 13A and 13B are views for showing a  
process of flattening [[a]] concave and convex parts  
formed on the surface of the InP layer in the case  
of that the InP layer grows in a structure having a  
concave structure.

35 Referring to FIG. 13A, a mesa structure  
61M is formed on an n-type InP substrate 61. An InP  
layer 62 is grown on the substrate 61 as it covers

the mesa structure 61M. As a result of this, a convex part corresponding to the mesa structure 61M is formed on a surface of the InP layer 62.

Therefore, in a process shown in FIG. 13B,  
5 wet etching is implemented to the InP layer 62 by the etchant including hydrochloric acid and acetic acid, and thereby a surface of the InP layer 62 is flattened.

C. Flattening concave structures formed on  
10 a surface of a growth layer not exceeding the height of a mask

FIGS. 14A and 14B are views for explaining a state in which a slope surface formed on a surface of the buried InP layer adjacent to a convex part  
15 formed on the substrate is flattened by a wet etching of the present invention when a buried InP layer grows on a substrate by using a selective growth mask. Such a slope surface is generated in case of the buried InP layer is formed  
20 at a lower position than a height of the selective growth mask.

Referring to FIG. 14A, a mesa structure 71M is formed on an n-type InP substrate 71 by using an SiO<sub>2</sub> pattern 72 as an etching mask.  
25 Besides, InP buried layers 73A and 73B are formed at the both sides of the mesa structure 71M by using the SiO<sub>2</sub> pattern 72 as a selectively growth mask. At that time, the InP layers 73A and 73B have heights which do not exceed the mesa structure 71M.  
30 A descent slope surface is formed on a side of the mesa structure 71M, because a vapor material becomes excessive when the InP buried layers 73A and 73B selectively grows on the selective growth mask 72.

In a process shown in FIG. 14B following  
35 the process shown in FIG. 14A, a wet etching process, in which the etchant of the present invention including hydrochloric acid and acetic acid is used,

is applied, and thereby the buried InP layers 73A and 73B are flattened.

D. Flattening concave structures including a semiconductor layer as an etching mask

5           As described above, a semiconductor including InGaAsP, InGaAs, Ga, or As has a quite late etching rate in case of the wet etching by using the etchant of the present invention including hydrochloric acid and acetic acid, as compared to  
10 the InP. Therefore, when the InP layer is flattened by using the etchant of the present invention, it is possible to use such InGaAsP or InGaAs semiconductor film as an etching mask.

FIG. 15A is a view for explaining a state  
15 in which a mesa structure 81M shouldering an InGaAsP pattern 82 is formed on an n-type InP substrate 81, and an InP buried layer 83 is grown as it covers the mesa structure 81M and the InGaAsP pattern 82.

A wet etching process, in which an etchant  
20 of the present invention including hydrochloric acid and acetic acid is used, is applied to a structure shown in FIG. 15A by using the InGaAsP pattern 82 as an etching mask as shown in FIG. 15B, and thereby it is possible to flatten the InP buried layer 83 as a  
25 surface of the InP buried layer 83 corresponds to a surface of the InGaAsP pattern 82.

Alternatively, as shown in FIGS. 16A and 16B, it is also possible to etch the InP buried layer 83 to such a depth as to reveal a portion  
30 below the InGaAsP pattern 82.

In the above description, flattening is defined as the formation of a surface comprised of at least one of the (100) surface, the (011) surface, or the (0-1-1) surface in the InP layer as a result  
35 of applying a wet etching in which the etchant including hydrochloric acid and acetic acid is used to a concave structure formed by the growth of an

InP layer. However, in the initial process of etching, a slope surface having a surface direction between the surface directions a slope surface and one of the (100) surface, the (011) surface, and the (0-1-1) surface appears, and changes gradually to one of the (100) surface, the (011) surface, and the (0-1-1) surface as the ~~etching~~ etching process. Therefore, flattening in the present invention is effective for a manufacturing process of an actual semiconductor device not only when the concave surface changes all the way to the (100) surface, the (011) surface, or the (0-1-1) surface but also when the concave surface stops changing halfway. That is, flattening in the present invention includes a case in which the InP concave surface not only changes into the (100) surface, the (011) surface, or the (0-1-1) surface but also is an intermediate slope surface.

Meanwhile, the etchant itself including hydrochloric acid, acetic acid, and hydrogen peroxide water has already been known to public. For instance, a Japanese Laid-Open Patent Application No. 10-65201 discloses an example in which an ~~that the~~ etchant including hydrochloric acid, acetic acid, and hydrogen peroxide water is used during a process of forming a mesa stripe. However, the etchant in the above patent application is used for arranging a side wall part of a convex part in a prior state to the crystal growth for a designated slope. Hence, it is not possible to assume that the etchant can be used for an effect of the present invention, namely flattening a concave structure formed by the crystal growth.

Furthermore, a Japanese Laid-Open Patent Application No. 2000-91303 discloses an example in that a side wall part of a mesa stripe formed by dry etching with the etchant including hydrochloric acid,



acetic acid, and hydrogen peroxide water. However, it is an object of an invention of the above patent application to eliminate a damage of a surface of the mesa stripe generated by the dry etching. Hence,  
5 it is not possible to assume that the etchant can be used for an effect of the present invention, namely flattening a concave structure formed by the crystal growth.

A description regarding a first embodiment  
10 of a manufacturing process of a laser diode having a BH structure according to the present invention will now be given, with reference of FIGS. 17A to 17E.

Referring to FIG. 17A, an InGaAsP/InGaAsP multi-quantum well active layer 102 is grown on an  
15 n-type InP substrate 101, a p-type InP clad layer 103 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 102, and a p-type InGaAs contact layer 104 is grown on the p-type InP clad layer 103.

In a process shown in FIG. 17B following  
20 the step shown in FIG. 17A, an active layer mesa stripe 101M is formed by dry etching with a SiO<sub>2</sub> film 105 as an etching mask. In an example shown in FIG. 17B, the active layer mesa stripe 101M is extended to a <011>-direction.

In a process shown in FIG. 17C following  
25 the step shown in FIG. 17B, Fe doped InP buried layers 106<sub>1</sub> and 106<sub>2</sub> grow at both sides of the mesa stripe 101M on the substrate 101 by the MOVPE method with the SiO<sub>2</sub> film 105 as a selective growth mask.  
30 The MOVPE process is implemented, in a state of a growth temperature of 630 °C and a growth pressure of 0.1 atmospheres, by using an element in a III group, an element in a V group, TMI<sub>n</sub>, PH<sub>3</sub>, and Cp<sub>2</sub>Fe as a material of a Fe dopant. In this embodiment,  
35 the thickness of the InP buried layers 106A and 106B are set as lowest parts of the InP buried layers 106<sub>1</sub> and 106<sub>2</sub> locate at higher positions than the a

p-type InGaAs contact layer 104. As a result of this, bulge parts 106a and 106b are formed on the InP buried layers 106<sub>1</sub> and 106<sub>2</sub>. The bulge parts 106a and 106b are adjacent to the SiO<sub>2</sub> film 105 on the mesa stripe 101M.

In a process shown in FIG. 17D following the process shown in FIG. 17C, wet etching is implemented by an etchant including hydrochloric acid, acetic acid, and water.

In the process shown in FIG. 17D, the mixture ratio of hydrochloric acid, acetic acid, and water in the etchant is set as 1:5:1. Typically, etching is carried out for 3 minutes at a liquid temperature of 23 °C. As a result of the etching, surfaces of the InP buried layers 106A and 106B become (100) surfaces as shown in FIG. 17D, and are flattened at a height of the p-type InGaAs layer 104.

In a process shown in FIG. 17E following the step shown in FIG. 17D, a structure shown in FIG. 17D is immersed in the hydrofluoric acid in one minute, and thereby the SiO<sub>2</sub> film 105 is removed by etching. After that, a p-side electrode 107 is formed on the p-type InGaAs layer 104 and an n-side electrode 108 is formed on a bottom surface of the substrate 101.

[[Since]] Because the buried layers 106<sub>1</sub> and 106<sub>2</sub> become flat surfaces in the process shown in FIG. 17E, the p-side electrode 107 is grown on a flat surface. Therefore, the breaking of the electrode as shown in FIG. 2 is not generated.

A description regarding a second embodiment of a manufacturing process of a laser diode having a BH structure according to the present invention will now be given, with reference of FIGS. 18A to 18C.

In FIGS. 18A to 18C, parts that are the same as the parts shown in the FIGS. 17A to 17E are

given the same reference numerals in, and explanation thereof will be omitted.

In this embodiment, in a process shown in FIG. 18A, equivalent processes to the processes shown in FIGS. 17A and 17B are implemented. As a result of this, the mesa stripe 101M is formed on the InP substrate 101 and the SiO<sub>2</sub> film 105 is removed by etching with [[the]] hydrofluoric acid.

In a process shown in FIG. 18B following the process shown in FIG. 18A, a Fe doped InP buried layer 106 crystal grows by the MOVPE method. The InP buried layer 106 has a slope surface and a bulged part corresponding to a configuration of the mesa stripe 101M. In the process shown in FIG. 18B, the Fe doped InP layer is formed as a part having a lowest thickness locates at a higher position than a height of the InGaAs contact layer.

In a process shown in FIG. 18C following the step shown in FIG. 18B, etching is implemented by the etchant including hydrochloric acid, acetic acid, and water. As a result of this, the slope surface of the Fe doped InP buried layer 106 is flattened, a ~~more-similar~~ surface [[than]] similar to the (100) surface is appeared appears.

In the process shown in FIG. 18C, etching of the InP buried layer 106 is improved, and thereby the buried layers 106<sub>1</sub> and 106<sub>2</sub> are formed at both sides of the mesa stripe 101M. As a result of the etching, the p-type InGaAs contact layer 104 is exposed. The exposed contact layer 104 works as an etching mask layer and the flat surface (100) having a same height as the p-type InGaAs contact layer 104 appears as a main surface of the buried layers 106<sub>1</sub> and 106<sub>2</sub>.

A description regarding a third embodiment of a manufacturing process of a laser diode having a pn buried structure according to the present

invention will now be given, with reference of FIGS. 19A to 19F.

Referring to FIG. 19A, an InGaAs/InGaAsP multi-quantum well active layer 112 is grown on an  
5 n-type InP substrate 111, a p-type InP clad layer 113 is grown on the InGaAs/InGaAsP multi-quantum well active layer 112, and a SiO<sub>2</sub> film 115 is grown on the p-type InP clad layer 113. An active mesa stripe 111M is formed by patterning based on dry  
10 etching.

In a process shown in FIG. 19B following the process shown in FIG. 19A, p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> grow at both sides of the mesa area 111M on the InP substrate 111 by the MOVPE method,  
15 where the SiO<sub>2</sub> film 115 is used as a selective growth mask. DMZn may be used as a p doping material. The p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> grow, as lowest parts of surfaces of the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> locate at higher positions than an  
20 upper surface of the InGaAs/InGaAsP multi-quantum well active layer and lower positions than an upper surface of the p-type InP clad layer 113 in the mesa stripe 111M.

In a process shown in FIG. 19C following  
25 the process shown in FIG. 19B, wet etching is implemented by the etchant including hydrochloric acid, acetic acid, and water. As a result of the wet etching, the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> are flattened. Thereby, surfaces of the p-type InP  
30 layers 116<sub>1</sub> and 116<sub>2</sub> are formed as corresponding to lowest areas of initial surfaces of the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub>. The surfaces of the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> are formed at higher positions than an upper surface of the  
35 InGaAs/InGaAsP multi-quantum well active layer 112 and lower positions than an upper surface of the p-type InP clad layer 113.

In a process shown in FIG. 19D following the process shown in FIG. 19C, n-type InP layers 117 crystal grow on the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub>.  
5 P-type InP layers 118 crystal grow on the n-type InP layers 117.

In a process shown in FIG. 19E following the process shown in FIG. 19D, the SiO<sub>2</sub> film 115 is removed by etching with hydrofluoric acid.

10 In a process shown in FIG. 19F following the process shown in FIG. 19E, a p-type InP clad layer 119 and a p-type InGaAs contact layer 120 grow by the MOVPE method.

Generally, a location of the n-type InP  
15 buried layer 117 should be controlled accurately in a pn buried structure for an electric current blocking. When a distance between the n-type InP buried layer 117 and the active layer 112 is long, an electric current leak pass is formed, and thereby  
20 an efficiency of electric current injection is reduced. When the distance between the n-type InP buried layer 117 and the active layer 112 is too short, there is no electric insulation between the n-type InP buried layer 117 and the n-type InP layer  
25 111 of a lower part of the active layer, and an electric current leaks through n-type InP layer. On the other hand, according to a method of this embodiment of the present invention, a position of a lower surface of the n-type InP buried layer 117 is  
30 decided only on a basis of the initial thickness of the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> shown in FIG. 19B, namely, only on a basis of growth time. Therefore, the position of the lower surface of the n-type InP buried layer 117 is not influenced by an index of a  
35 surface of crystal growth generated by the MOVPE method. It is difficult for the surface of the crystal growth to control a position of the surface

of the crystal growth because the surface of the crystal growth can be easily changed on growth conditions such as a growth temperature or pressure. Besides, the n-type InP buried layer 117 is not  
5 influenced by a surface direction dependency of the efficiency of n-type-dopant absorption in the InP layer because the n-type InP buried layer 117 grows on the p-type InP layers 116<sub>1</sub> and 116<sub>2</sub> having (100) surface. Hence, it is possible to form the n-type  
10 InP layer 117 having a constant density on whole surfaces.

A description regarding a fourth embodiment of a manufacturing process of a laser diode having a pn buried structure according to the  
15 present invention will now be given, with reference of FIGS. 20A to 20G.

Referring to FIG. 20A, the InGaAsP/InGaAsP multi-quantum well active layer 112 is grown on the n-type InP substrate 111, the p-type InP clad layer  
20 113 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 112, and the p-type InGaAs contact layer 114 is grown on the p-type InP clad layer 113. A mesa stripe 111M is formed on the substrate 111 by dry etching in which the SiO<sub>2</sub> film 115 is used as a  
25 mask. In the FIG. 20A, the SiO<sub>2</sub> film 115 is removed by etching with hydrofluoric acid.

In a process shown in FIG. 20B following the process shown in FIG. 20A, a p-type InP layer 116 crystal grows on a structure shown in FIG. 22A.  
30 In the process shown in FIG. 22B, a thickness of the p-type InP layer 116 is set as a lowest part of the surface of the p-type InP layer 116 locates at a higher position than an upper surface of the InGaAsP/InGaAsP multi-quantum well active layer 112  
35 and at a lower position than a lower surface of a p-InGaAs contact layer 114.

In a process shown in FIG. 20C following

the process shown in FIG. 20B, wet etching by using an etchant of a mixed liquid including hydrochloric acid, acetic acid, and water is implemented, and thereby the p-type InP layer 116 is flattened.

5 Thereby, flat surfaces of the p-type InP layers 116 is formed as corresponding to lowest areas of initial surfaces of the p-type InP layers 116. The flat surfaces of the p-type InP layers 116 is formed at a higher position than the InGaAsP/InGaAsP multi-  
10 quantum well active layer 112 and at a lower position than the p-type InGaAs layer 114. As a result of a process of flattening shown in FIG. 22C, the InP layer 116 is divided into InP areas 116<sub>1</sub> and 116<sub>2</sub> by the mesa stripe as a border.

15 In a process shown in FIG. 20D following the process shown in FIG. 20C, an n-type InP buried layer 117A grows on a structure shown in FIG. 20C by the MOVPE method. A thickness of the n-type InP layer 117A is decided as a lowest part of a surface  
20 of the InP layer 117A locates at a lower position than a lower surface of the InGaAs contact layer 114.

In a process shown in FIG. 20E following the process shown in FIG. 20D, the n-type InP buried layer 117A is wet etched by the etchant including  
25 hydrochloric acid, acetic acid, and water. As a result of this, a surface of the n-typed InP layer 117A is flattened at a lower position than the InGaAs contact layer 114.

In a process shown in FIG. 20F following  
30 the process shown in FIG. 20E, a p-type InP buried layer 118A grows as covering the InGaAs contact layer 114, by the MOVPE method.

In a process shown in FIG. 20G, the p-type InP buried layer 118A shown in FIG. 20F is wet  
35 etched by the etchant including hydrochloric acid, acetic acid, and water, and thereby a height of an upper surface of the InP buried layer 118A is the

same as a height of the InGaAs contact layer 114.

According to this embodiment, the film thickness of the p-type InP buried layer 116A is controlled in the process shown in FIG. 20B. Hence, a location of the lower surface of the n-type InP buried layer 117A is controlled. Furthermore, the initial film thickness of the n-type InP buried layer 117A is controlled in the process shown in FIG. 20D. Hence, a location of the upper surface of the n-type InP buried layer 117A is controlled. Therefore, the electric current blocking structure can be manufactured accurately.

A description regarding a fifth embodiment of a manufacturing process of a laser diode having a pn buried structure according to the present invention will now be given, with reference of FIGS. 21A to 21G.

Referring to FIG. 21A, the InGaAsP/InGaAsP multi-quantum well active layer 112 is grown on the n-type InP substrate 111, the p-type InP clad layer 113 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 112, and the p-type InGaAs contact layer 114 is grown on the p-type InP clad layer 113. The mesa stripe 111M including the p-type InP clad layer 113 and the p-type InGaAs contact layer 114, is formed on the substrate 111 by dry etching in which the SiO<sub>2</sub> film 115 is used as a mask. The SiO<sub>2</sub> film 115 is removed by etching with hydrofluoric acid.

In a process shown in FIG. 21B following the process shown in FIG. 21A, the p-type InP layer 116 crystal grows on the structure shown in FIG. 21A. In the process shown in FIG. 21B, a thickness of the p-type InP layer 116 is set as a lowest part of a surface of the p-type InP layer 116 locates at a higher position than an upper surface of the InGaAsP/InGaAsP multi-quantum well active layer 112



and at a lower position than a lower surface of the p-InGaAs contact layer 114.

In a process shown in FIG. 21C following the process shown in FIG. 21B, wet etching by using  
5 the etchant of the mixed liquid including hydrochloric acid, acetic acid, and water is implemented, and thereby the p-type InP layer 116 is flattened. Thereby, the flat surface of the p-type InP layers 116 is formed as corresponding to the  
10 lowest area of an initial surface of the p-type InP layers 116. The flat surface of the p-type InP layers 116 is formed at a higher position than an upper surface of the InGaAsP/InGaAsP multi-quantum well active layer 112 and at a lower position than  
15 the p-type InGaAs layer 114. As a result of a process of flattening shown in FIG. 21C, the InP layer 116 is divided into the InP areas 116<sub>1</sub> and 116<sub>2</sub> by the mesa stripe as a border. Thus, the processes shown in FIGS. 21A to 21C respectively  
20 correspond to the processes shown in FIGS. 20A to 20C.

In a process shown in FIG. 21D, an n-type InP layer 117B and a p-type InP buried layer 118B grow in turn by the MOVPE method. ~~Thickness~~  
25 Thicknesses of the n-type InP layer 117B and the p-type InP buried layer 118B are set, as a lowest part of a surface of the n-type InP layer 117B locates at a lower position than a lower surface of the n-type InP layer 117B and a lowest part of a surface of the  
30 p-type InP layer 118B locates at a higher position than the InGaAs layer 114.

In a process shown in FIG. 21E following the process shown in FIG. 21D, the n-type InP layer 117B and the p-type InP buried layer 118B are wet  
35 etched by the etchant of the mixed liquid including hydrochloric acid, acetic acid, and water. In the process of the wet etching, surfaces of the n-type

InP layer 117B and the p-type InP buried layer 118B are flattened by using the InGaAs layer 114 as an etching mask.

In a process shown in FIG. 21F following  
5 the process shown in FIG. 21E, the InGaAs layer 114 is removed by etching with the mixed liquid including hydrofluoric acid and nitric acid. In a process shown in FIG. 21G, a p-type InP clad layer 119 and a p-type InGaAs contact layer 120 crystal  
10 grow in turn by the MOVPE method.

In the process shown in FIG. 21B, a position of a lower surface of the n-type InP buried layer 117 can be controlled by controlling a thickness of the n-type InP buried layer 116.

15 A description regarding a sixth embodiment of a manufacturing process of a laser diode having a pn buried structure according to the present invention will now be given, with reference of FIGS. 22A to 22D. In FIGS. 22A to 22D, parts that are the  
20 same as the parts described above are given the same reference numerals in, and explanation thereof will be omitted.

Referring to FIG. 22A, the InGaAsP/InGaAsP multi-quantum well active layer 112 is grown on the  
25 n-type InP substrate 111, the p-type InP clad layer 113 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 112, and the p-type InGaAs contact layer 114 is grown on the p-type InP clad layer 113. The mesa stripe 111M is formed on the substrate 111  
30 by dry etching in which the SiO<sub>2</sub> film 115 is used as a mask.

In a process shown in FIG. 22B following the process shown in FIG. 22A, the p-type InP buried layer 116, the n-type InP buried layer 117, and the  
35 p-type InP layer 118 grow in turn by the MOVPE method, in a state where the SiO<sub>2</sub> film 115 is formed on the mesa stripe 111M. The MOVPE process shown in

FIG. 22B is implemented in a state of a growth temperature of 550 °C, and a growth pressure of 0.1 atmospheres, by using a material in a III group, a material in a V group, TMI<sub>n</sub>, PH<sub>3</sub>, DMZn, and SiH<sub>4</sub> as p-type and n-type-dopant materials and adding 10 CCM of CH<sub>3</sub>Cl. With a combination of such low temperature growth and adding of a gas of a chlorine group, each buried layer is controlled to bulge-grow and rather grows from a mesa bottom surface [[to]]  
10 in the <100>-direction.

In a process shown in FIG. 22B, thickness of the p-type InP layer 116 and the n-type InP layer 117 are set as a contact position between a lower surface of the n-type InP layer 117 and the mesa stripe 111M locates at a higher position than an upper surface of the active layer 112, and a contact position between an upper surface of the n-type InP layer 117 and the mesa stripe 111M locates at a lower position than a lower surface of the p-type  
15 InGaAs contact layer 114.

In a process shown in FIG. 22C following the process shown in FIG. 22B, wet etching is implemented by using the etchant of the mixed liquid including hydrochloric acid, acetic acid, and water and using the SiO<sub>2</sub> film 115 as a mask. As a result  
25 of this, the p-typed InP layer 118 is flattened, and thereby a flat surface corresponding to an upper surface of the InGaAs clad layer 114 is obtained.

In a process shown in FIG. 22D, the SiO<sub>2</sub> film 115 is removed by etching with a mixed liquid including hydrofluoric acid and hydrogen peroxide water.  
30

In this embodiment, it is possible to obtain a flat growth surface with buried growth of one time, and thereby it is possible to greatly  
35 simplify the manufacturing process of the laser diode.

A description regarding a seventh embodiment of a manufacturing process of a laser diode having a ridge structure according to the present invention will now be given, with reference of FIGS. 23A to 23E.

Referring to FIG. 23A, an InGaAs/InGaAsP multi-quantum well active layer 122 is grown on an n-type InP substrate 121, a p-type InP clad layer 123 is grown on the InGaAs/InGaAsP multi-quantum well active layer 122, and a p-type InGaAs contact layer 124 is grown on the p-type InP clad layer 123. A ridge stripe 123M is formed on the clad layer 123 by patterning on a basis of dry etching in which a SiO<sub>2</sub> film 125 is used as a mask. Furthermore, in the process shown in FIG. 23A, the SiO<sub>2</sub> film 125 is removed by etching with hydrofluoric acid.

In a process shown in FIG. 23B following the process shown in FIG. 23A, the n-type InP layer 126 crystal grows. At that time, a thickness of the n-type InP layer 126 is set as an upper surface of the n-type InP layer 126 locates at a lower position than a lower surface of the p-type InGaAs layer 124.

In a process shown in FIG. 23C following the process shown in FIG. 23B, wet etching is implemented by the etchant of the mixed liquid including hydrochloric acid, acetic acid, and water and with the InGaAs contact layer 124 as a mask. As a result of this, a surface of the n-type InP layer 126 is flattened, and thereby a position of an upper surface of the n-type InP layer 126 locates at a lower position than a position of a lower surface of the p-type InGaAs layer 124.

In a process shown in FIG. 23D following the process shown in FIG. 23C, a p-type InP layer 127 is formed by the MOVPE method. The p-type InP layer 127 has a thickness as a lowest area of an

upper surface of the p-type InP layer 127 is higher than an upper surface of the p-type InGaAs layer 124.

In a process shown in FIG. 23E following the process shown in FIG. 23D, wet etching is  
5 implemented by the etchant including hydrochloric acid, acetic acid, and water and with the InGaAs contact layer 124 as a mask. And thereby the InP layer 127 is flattened. As a result of this, the p-type InP layer 127 has a surface corresponding to  
10 the surface of the InGaAs contact layer 124.

It is necessary that a surface position of the n-type InP buried layer 126 is controlled carefully in order to realize an effective electric current blocking for a laser diode having the ridge  
15 structure. For instance, if a distance between the n-type InP layer 126 and p-type InGaAs contact layer 124 is long, the distance acts as an electric leak pass. In a method of this embodiment, a designated and effective electric current blocking is realized  
20 by only controlling a thickness of the n-type InP buried layer 126 in the process shown in FIG. 23B.

A description regarding a eighth embodiment of a manufacturing process of a laser diode having a ridge structure according to the  
25 present invention will now be given, with reference of FIGS. 24A to 24F. In FIGS. 24A to 24F, parts that are the same as the parts described above are given the same reference numerals in, and explanation thereof will be omitted.

30 Referring to FIG. 24A, the InGaAs/InGaAsP multi-quantum well active layer 122 is grown on the n-type InP substrate 121, the p-type InP clad layer 123 is grown on the InGaAs/InGaAsP multi-quantum well active layer 122, and the p-type InGaAs contact  
35 layer 124 is grown on the p-type InP clad layer 123. The ridge stripe 123M is formed on the clad layer 123 by dry etching in which the SiO<sub>2</sub> film 125 is

used as a mask.

In a process shown in FIG. 24B following the process shown in FIG. 24A, the n-type InP layer 126 is formed by the MOVPE method in a state where  
5 the SiO<sub>2</sub> film 125 remains as a selective growth mask. The n-type InP layer 126 has a thickness as an upper surface of the n-type InP layer 126 is lower than a lower surface of the p-type InGaAs contact layer 124.

In a process shown in FIG. 24C following  
10 the process shown in FIG. 24B, wet etching is implemented by the etchant including hydrochloric acid, acetic acid, and water [[. And]] and thereby the n-type InP layer 126 has a flat surface as the flat surface locates at a lower position than the p-type InGaAs layer 124.  
15

In a process shown in FIG. 24D following the process shown in FIG. 24C, the p-type InP layer 127 is formed by the MOVPE method in a state the SiO<sub>2</sub> film 125 remains as a selective growth mask.  
20 The p-type InP layer 127 has a thickness as a lowest area of the upper surface of the p-type InP layer 127 is higher than a height of the p-type InGaAs layer 124.

In a process shown in FIG. 24E following  
25 the process shown in FIG. 24D, wet etching is implemented by the etchant including hydrochloric acid, acetic acid, and water, and thereby the p-type InP layer 127 is flattened. A flattening process shown in FIG. 24E is implemented in a state where  
30 the SiO<sub>2</sub> film 125 remains on the contact layer 124. As a result of this, a height of a flat surface of the p-type InP layer 127 corresponds to the height of an upper surface of the contact layer 124.

In a process shown in FIG. 24F following  
35 the process shown in FIG. 24E, the SiO<sub>2</sub> film 125 is removed by etching with the ~~etchant~~ etchant of the mixed liquid including hydrofluoric acid and a

hydrogen peroxide water.

A description regarding a ninth embodiment of a manufacturing process of an optical wave guide having a branch according to the present invention will now be given, with reference of FIGS. 25A to 25E.

Referring to FIG. 25A, an InGaAsP/InGaAsP multi-quantum well active layer 202 is grown on an n-type InP substrate 201, and an InP clad layer 203 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 202. Dry etching is implemented with [[a]] an SiO<sub>2</sub> pattern 205 having a branch of a Y shape, and thereby an effect of the dry etching reaches the InP substrate 201. As a result of this, a mesa stripe 201M having a Y shape corresponding to the SiO<sub>2</sub> pattern 205 is formed on the substrate 201.

In a process shown in FIG. 25B following the process shown in FIG. 25A, a Fe doped InP buried layer 206 is formed by the MOVPE method in a state where the SiO<sub>2</sub> pattern 205 remains as a selective growth mask. The Fe doped InP buried layer 206 has a thickness as the lowest part of the Fe doped InP layer 206 is higher than the upper surface of the clad layer 203 of the mesa stripe 201M. As a result of the process shown in FIG. 25B, the Fe doped InP buried layer 206 is formed on the InP substrate 201 as the mesa stripe 201M having a Y shape is clamped at a side of mesa stripe 201M.

In a process shown in FIG. 25C, wet etching is implemented by the etchant of mixed liquid including hydrochloric acid, acetic acid, and water. As a result of this, a surface of the Fe doped InP buried layer 206 is flattened as the surface corresponds to an upper surface of the InP clad layer 203 of the highest part of the mesa stripe 201M.

In a process shown in FIG. 25D, the SiO<sub>2</sub>

pattern 205 is removed by etching with a mixed liquid including hydrofluoric acid and a hydrogen peroxide water. In a process shown in FIG. 25E, the Fe doped InP layer 207 grows by the MOVPE method.

5 At that time, a surface of the Fe doped InP layer 207 is flattened because the InP clad layer 206 and the InGaAs layer 204 make a flat surface made of (100) surface.

As described with FIG. 3, according to the  
10 conventional process, the buried InP layer may overhang to the mask at a part of the branch when the InP buried layer grows around the stripe having the branch. On the other hand, according to this embodiment of the present invention, the overhung  
15 part can be removed by wet etching of the InP buried layer 206 in the process shown in FIG. 25C. As a result of this, in the process shown in FIG. 25E, even if the InP layer 207 is grown, a cave is not generated.

20 A description regarding a tenth embodiment of a manufacturing process of an optical wave guide having a BH buried structure and a branch according to the present invention will now be given, with reference of FIGS. 26A to 26C. In FIGS. 26A to 26C,  
25 parts that are the same as the parts described above are given the same reference numerals in, and explanation thereof will be omitted.

Referring to FIG. 26A, an InGaAsP/InGaAsP multi-quantum well active layer 202 is grown on an  
30 n-type InP substrate 201, an InP clad layer 203 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 202, and an InGaAs layer 204 is grown on the InP clad layer 203. Dry etching is implemented with [[a]] an SiO<sub>2</sub> pattern 205, and  
35 thereby a mesa stripe 201M having Y shape is formed. In the process shown in FIG. 26A, after the mesa stripe is formed, the SiO<sub>2</sub> pattern 205 is removed by



etching with hydrofluoric acid.

In a process shown in FIG. 26B following the process shown in FIG. 26A, a Fe doped InP buried layer 206 is formed by the MOVPE method. The Fe  
5 doped InP buried layer 206 is formed as the lowest surface of the Fe doped InP layer 206 is higher than the upper surface of the p-type InGaAs layer 204. As a result of the process shown in FIG. 26B, the Fe doped InP buried layer 206 has a concave and convex  
10 part corresponding to a stripe pattern 201M having a Y shape as a base, on a surface of the Fe doped InP buried layer 206.

In a process shown in FIG. 26C, wet etching is implemented by the etchant of mixed  
15 liquid including hydrochloric acid, acetic acid, and water. As a result of this, the InP buried layer 206 is flattened.

In the process of flattening shown in FIG. 26C, the p-type InGaAs layer 204 acts as an etching  
20 mask. As a result of this, the Fe doped InP layer 206 has a surface which substantially corresponds to a surface of the InGaAs layer 204. Therefore, in a process following to the process shown in FIG. 26C, when another semiconductor layer or an electrode  
25 pattern is formed, a problem is not generated because it is formed on a flat surface.

A description regarding an eleventh embodiment of a manufacturing process of a semiconductor device including a process of  
30 selective growth of an active layer according to the present invention will now be given, with reference of FIGS. 27A to 27C.

Referring to FIG. 27A, a SiO<sub>2</sub> pattern 212 is formed as a width of the SiO<sub>2</sub> pattern 212 varies  
35 along a <0-11>-direction. The SiO<sub>2</sub> pattern 212 exposes a substrate area which extends [[to]] in the <0-11>-direction on a surface of the n-type InP

substrate 211.

In a process shown in FIG. 27B following the process shown in FIG. 27A, the MOVPE method is implemented by using the SiO<sub>2</sub> film as a mask. And thereby, an n-type InP layer 213 is grown on the InP substrate 211, an InGaAsP/InGaAsP multi-quantum well active layer 214 is grown on the n-type InP layer 213, and a p-type InP clad layer 215 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 214. In the selective growth in which the SiO<sub>2</sub> pattern 212 is a mask, a material density increases on the SiO<sub>2</sub> pattern 212 where the semiconductor layer does not grow. As a result of this, a material is supplied excessively in the substrate area which extends [[to]] in the <0-11>-direction where the SiO<sub>2</sub> pattern 212 is broken. Such excessive supply of the material depends on a ratio of covering of the SiO<sub>2</sub> film, namely a width of the SiO<sub>2</sub> pattern 212. Hence, as the width becomes wide, an amount of an excessive supply of a material increases and the thickness of the semiconductor layers 213 to 215 increases. Since the width of the SiO<sub>2</sub> pattern 212 varies along the <0-11>-direction, the thickness of the semiconductor layers 213 to 215 varies to the <0-11>-direction.

In a process shown in FIG. 27C, wet etching is implemented by the etchant of mixed liquid including hydrochloric acid, acetic acid, and water, and thereby the p-type InP layer 215 is flattened at a height corresponding to the lowest surface part of the upper surface of the p-type InP layer 215.

When a concave structure is generated in the selective growth including such the active layer 214, a problem is generated in an electric current blocking buried growth process or an electrode forming process. However, according to this

embodiment, it is possible to flatten such the concave structure, and thereby the above-mentioned problem can be avoided.

A description regarding a twelfth  
5 embodiment of a manufacturing process of a semiconductor device including a selective growth process of an active layer will now be given, with reference of FIGS. 28A to 28E. In FIGS. 28A to 28E,  
10 parts that are the same as the parts described above are given the same reference numerals in, and explanation thereof will be omitted.

Referring to FIG. 28A, the SiO<sub>2</sub> film pattern 212 is formed on the InP substrate 211 as a width of the SiO<sub>2</sub> pattern 212 varies along an  
15 opening part which exposes the substrate 211. In a process shown in FIG. 28B following the process shown in FIG. 28A, dry etching is implemented to the InP substrate 211 in a state where the SiO<sub>2</sub> pattern 212 is a mask. ~~And thereby~~ Thereby, a groove 211A  
20 having a depth of approximately 1  $\mu$ m is formed on a surface of the InP substrate 211.

In a process shown in FIG. 28C following the process shown in FIG. 28B, the InGaAsP/InGaAsP multi-quantum well active layer 213 and the p-type  
25 InP clad layer 215 are formed by the MOVPE method as the groove 211A is buried. At that time, a thickness of the p-type InP clad layer 215 is set as a lowest surface part of an upper surface of the InP clad layer 215 is higher than a surface of the n-  
30 type InP substrate 211. ~~[[Since]]~~ Because a width of the SiO<sub>2</sub> pattern 212 varies along the <011>-direction, a variation of a film thickness is generated ~~[[to]]~~ in the <011>-direction on the InP clad layer 215.

35 In a process shown in FIG. 28D following the process shown in FIG. 28C, the SiO<sub>2</sub> pattern 212 is eliminated by etching with the mixed liquid

including hydrofluoric acid and a hydrogen peroxide water. In a process shown in FIG. 28E following the process shown in FIG. 28D, wet etching is implemented by the etchant of a mixed liquid including hydrochloric acid, acetic acid, and water.

As a result of the wet etching, the InP clad layer 215 is flattened, and thereby a flat surface corresponding to the InP substrate 211 as an upper surface of the clad layer 215 is achieved.

A description regarding a thirteenth embodiment of a manufacturing process of a multi layer optical wave guide will now be given, with reference of FIGS. 29A to 29E. In FIGS. 29A to 29E, parts that are the same as the parts described above are given the same reference numerals in, and explanation thereof will be omitted.

Referring to FIG. 29A, the InGaAsP/InGaAsP multi-quantum well active layer 222 is grown on the n-type InP substrate 221 and the InP clad layer 223 is grown on the InGaAsP/InGaAsP multi-quantum well active layer 222. After that, a first wave guide mesa stripe pattern 212M is formed by dry etching in a state where the SiO<sub>2</sub> pattern 225 is a mask. In an example shown in FIG. 29A, the first wave guide mesa stripe pattern 212M has a branch Y shape.

In a process shown in FIG. 29B following the process shown in FIG. 29A, the Fe doped InP buried layer 226 grows by the MOVPE method in a state where the SiO<sub>2</sub> pattern 225 is a selective growth mask, as the first wave guide mesa stripe pattern 212M is buried. In the process shown in FIG. 29B, a thickness of the Fe doped InP layer 226 is set as a lowest part of the Fe doped InP layer 226 is higher than an upper part of the first wave guide mesa stripe pattern 212M.

In a process shown in FIG. 29C following the process shown in FIG. 29B, wet etching is

implemented by the etchant of a mixed liquid including hydrochloric acid, acetic acid, and water, and thereby a surface of the InP layer 226 is flattened.

5           In a process shown in FIG. 29D following the process shown in FIG. 29C, the SiO<sub>2</sub> pattern 225 is removed by etching with the mixed liquid including hydrofluoric acid and a hydrogen peroxide water. In a process shown in FIG. 29E following the  
10 process shown in FIG. 29D, the InP clad layer 227 is grown on the InP layer 226, the InGaAsP/InGaAsP multi-quantum well active layer 228 is grown on the InP clad layer 227, and the InP clad layer 229 is grown on the InGaAsP/InGaAsP multi-quantum well  
15 active layer 228. After that, dry etching is implemented in a state where the SiO<sub>2</sub> pattern 230 formed on the InP clad layer 229 is a mask, and thereby a second wave guide mesa stripe pattern 227M is formed on the InP layer 226.

20           In a process shown in FIG. 29F, the Fe doped InP buried layer 231 is formed by the MOVPE method in a state where the SiO<sub>2</sub> pattern 230 is used as a selective growth mask. At that time, the Fe doped InP buried layer 231 has a thickness in a  
25 state where the lowest part of the Fe doped InP buried layer 231 is higher than the upper part of the second wave guide mesa stripe pattern 227M.

          In a process shown in FIG. 29G following the process shown in FIG. 29F, wet etching is  
30 implemented by the etchant of a mixed liquid including hydrochloric acid, acetic acid, and water, and thereby the Fe-doped In layer 231 is flattened. After that, the SiO<sub>2</sub> pattern 230 is removed by etching with the mixed liquid including hydrofluoric  
35 acid and a hydrogen peroxide water, and thereby an optical wave guide having a double layer structure is achieved.

When the optical wave guide is multiple-grown, it is necessary that a surface is flat after respective layers are formed. However, in this embodiment, a thickness of the InP layer 226 or 231 is controlled, and flattening is implemented as corresponding to a lowest surface part of these layers. Such control of the layer thickness is not possible by polishing.

According to the above-described embodiments, the mixed liquid including hydrochloric acid, acetic acid, and water is used as the etchant. For flattening by the etchant in the present invention, a composition ratio of the etchant of hydrochloric acid, acetic acid, and water is set as 1:X:Y, where a density concentration parameter X is in a range of 0 to 20 and a density concentration parameter Y is in any range, is effective. Besides, if a mixed liquid of hydrochloric acid, acetic acid, hydrofluoric acid, and water is used as the etchant, a composition ratio of the etchant of hydrochloric acid, acetic acid, hydrogen peroxide water, and water is set as 1:X:Y:Z, where a density concentration parameter X is in a range of 0 to 20, a density concentration parameter Y is in a range of 0 to 0.3, with no range requirement for a density concentration parameter Z, is effective to achieve an equivalent effect.

The present invention is not limited to these embodiments, but various variations and modifications may be made without departing from the scope of the present invention. Particularly, [[since]] because the present invention is based on the flattening by anisotropy etching against a concave structure of the grown InP layer as a principle, the present invention can be applied to not only an optical semiconductor device but also any semiconductor device whose material is InP.

This ~~patent~~ application is based on  
Japanese priority patent application No. 2000-393318  
filed on December 25, 2000, the entire contents of  
which are hereby incorporated by reference.